

ILLUMINATION SYSTEM WITH A PLURALITY OF LIGHT SOURCES

Abstract

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The invention concerns an illumination system for wavelengths ≤ 193 nm,
especially for EUV-lithography with

a plurality of light sources

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a mirror device for creating secondary light sources comprising several mirrors,
said mirrors are comprising raster elements.

The invention is characterized in that

15 the plurality of light sources are coupled together in order to illuminate the exit
pupil of the illumination system up to a predetermined degree of filling.